## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:

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Examiner:

Marianne L. Padgett

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## RESPONSE UNDER 37 C.F.R. § 1.114

Sir:

In connection with the filing of a request for continued consideration (RCE), and in response to the Advisory Action dated November 20, 2009 and the Final Office Action dated September 15, 2009, Applicants submit the following amendments and remarks for entry as a matter of record in the above referenced application. Applicants respectfully request entry of the amendment submitted in the § 1.116 Response dated November 16, 2009. The status indicators of the present amendments indicate the status of the claim as if the amendments in the § 1.116 Response have been entered.

## CERTIFICATE OF ELECTRONIC FILING

I hereby certify that this correspondence is being deposited with the United States Patent & Trademark Office via Electronic Filing through the United States Patent and Trademark Office e-business website, on December 15, 2009.

Dated: December 15, 2009